



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT application of	) RESPONSE UNDER 37 CFR
Nobuo SHIMAZU et al.	) 1.116 – EXPEDITED ) PROCEDURE EXAMING ) GROUP 2881
Application No. 09/732,927	) )
Filed: December 11, 2000	) Examiner: T. NGUYEN
For: MANUFACTURING METHOD OF MASK FOR ELECTRON BEAN PROXIMITY EXPOSURE AND MASK	) ) )

## **CERTIFICATE OF TRANSMISSION**

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage for first class mail in an envelope addressed to: Mail Stop AF, Commissioner for Patents, P.O. Box 1450, Alexandria, Virginia 22313-1450, or being facsimile transmitted to the USPTO at (703) 872-9319, on May (33, 2003).

AMENDMENT AFTER FINAL REJECTION

Mail Stop AF Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The following remarks are presented in response to the Examiner's final Office Action mailed February 10, 2003, in connection with the above-identified application.